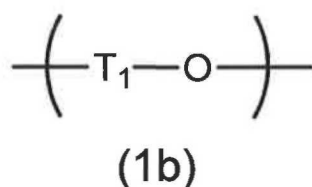
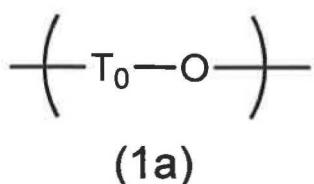


ABSTRACT

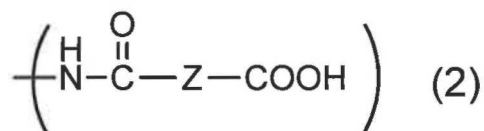
RESIN COMPOSITION, METHOD FOR FORMING PATTERN USING THE SAME,
AND METHOD FOR SYNTHESIZING POLYMER

5 There are provided a resin composition comprising a novel polymer, a method for forming a pattern using the resin composition, and a method for synthesizing the polymer. A resin composition for forming an insulating film comprising a polymer having a structural unit of the following formula (1a) and a structural unit of the following formula (1b); and an organic solvent:

10



wherein T_0 is a divalent organic group containing at least one arylene group in which at least one hydrogen atom is substituted with an amino group; and T_1 is a divalent
15 organic group containing at least one arylene group having at least one substituent, wherein the substituent is a substituent of the following formula (2):



wherein Z is a divalent, aliphatic, aromatic, or alicyclic group optionally having a
20 substituent.